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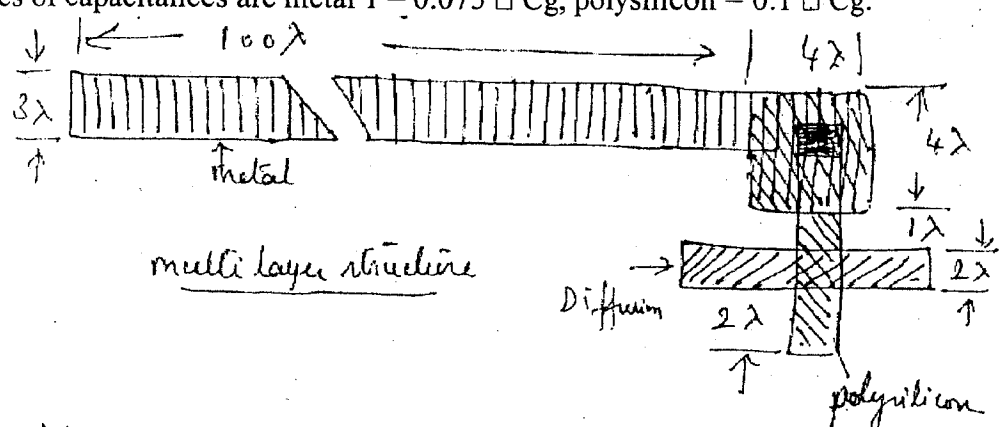
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M.Tech. Degree Examination, Dec. 07 / Jan. 08
CMOS VLSI Design

Time: 3 hrs.

Max. Marks:100

Note : Answer any FIVE full questions.

1. a. Briefly explain the second order effects in MOSFET. (07 Marks)
 b. With neat diagram and transfer characteristics, explain the CMOS inverter. Obtain the necessary expressions for the same. (08 Marks)
 c. Calculate the native threshold voltage for an n-transistor at 300° K for a process with a silicon substrate with $N_A = 1.8 \times 10^{16} / \text{cc}$, $t_{\text{ox}} = 200 \text{ \AA}$. Assume $\phi_{\text{ms}} = -0.9 \text{ V}$, $Q_{\text{fc}} = 0$, $\eta_1 = 1.45 \times 10^{10} / \text{cc}$. (05 Marks)
2. a. With relevant response curves, explain the transmission gate output characteristics for change in control input and for change in switched input. (06 Marks)
 b. Obtain the scaling factors for the following – i) Gate delay ii) Current density iii) Switching energy. (06 Marks)
 c. With neat fabrication sketches. Explain the silicon on insulator (SOI) CMOS process. (08 Marks)
3. a. Explain the CMOS process enhancement with reference to i) metal interconnect ii) polysilicon /refractory metal inter connect. (06 Marks)
 b. For the following structure obtain values for C_m , C_p , C_g and C_T . Given that the relative values of capacitances are metal 1 = 0.075 \square C_g , polysilicon = 0.1 \square C_g .

 Fig. Q 3(b) (08 Marks)
 c. Obtain the CMOS circuit and stick diagram for the following function $f = (A + BC)D$. (06 Marks)
4. a. With a neat diagram, obtain the parasitic device capacitance in CMOS 2 input NOR gate for $k_N = 4$ KP and explain the circuit operation. (06 Marks)
 b. Differentiate between AOI logic and OAI logic with a suitable example of each. (08 Marks)
 c. For the given function $F = AB + A'C' + AB'C$ obtain the i) CMOS TG realization ii) CMOS transistor realization. (06 Marks)

- 5 a. With a neat gate level schematic and CMOS circuit explain the CMOS SR latch circuit based on clocked NOR2 gates. (06 Marks)
- b. Briefly discuss the charge storage and charge leakage in n mos pass transistor. (06 Marks)
- c. Calculate the worst case time for the following data given $V_{TO} = 0.8 \text{ V}$, $v = 0.4 \text{ V}^{1/2}$, $|\phi_F| = 0.6 \text{ V}$, $C_{OX} = 0.065 \text{ fF}/\mu\text{m}^2$, $C_{\text{metal}}^1 = 0.036 \text{ fF}/\mu\text{m}^2$, $C_{\text{poly}}^1 = 0.055 \text{ fF}/\mu\text{m}^2$, $C_{jo} = 0.095 \text{ fF}/\mu\text{m}^2$, $C_{josw} = 0.2 \text{ fF}/\mu\text{m}$, $I_{\text{leakage}} = 0.85 \text{ pA}$.

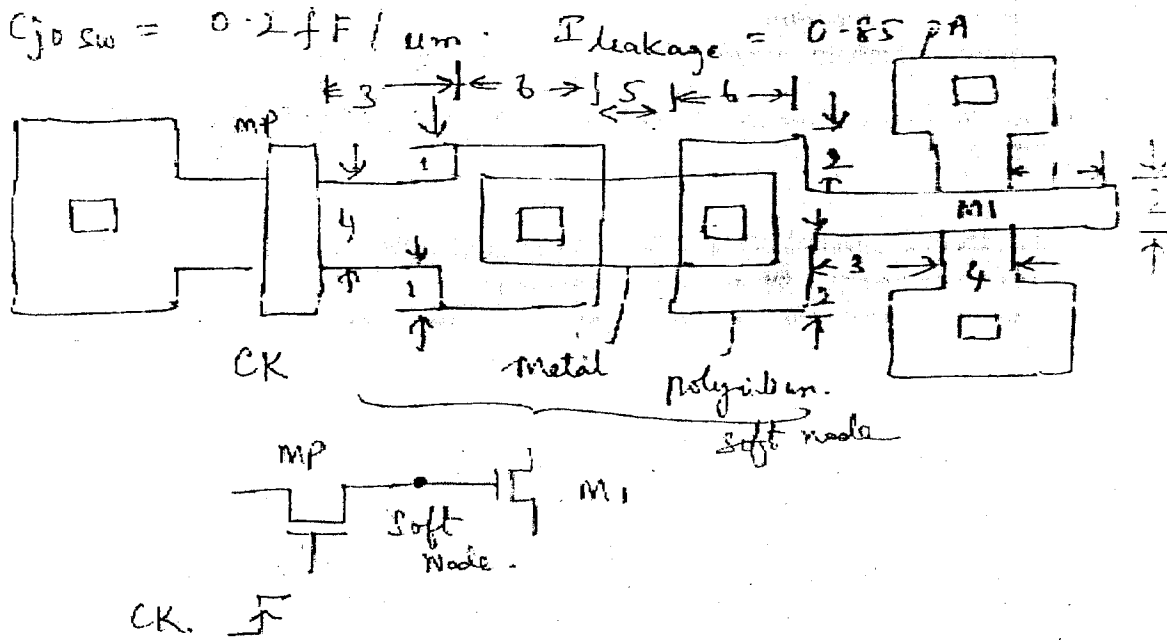


Fig. Q 5(c)

(08 Marks)

- 6 a. Bring out the difference between Ratioed logic and ratio less logic with respect to 3 bit shift register. (06 Marks)
- b. Dynamic CMOS logic circuit cannot be cascaded. Justify the statement. (06 Marks)
- c. With relevant diagram, explain the NORA CMOS logic [NP – Domino logic]. (08 Marks)
- 7 a. Explain with necessary expressions and transfer characteristics the differential amplifier. (08 Marks)
- b. Discuss the general principle of the Band-gap reference and hence obtain expression for V_{BE} . (07 Marks)
- c. Briefly explain the clock distribution network with relevant sketches. (05 Marks)
- 8 Write short notes on : (10 Marks)
- Differential inverter
 - Complementary pass transistor logic (CPL)
 - Domino CMOS logic
 - Latch up phenomenon.

(10 Marks)
